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U.S. PATENT DOCUMENTS					
EXAMINER INITIAL	DOCUMENT NO.	PUBLICATION DATE	INVENTOR NAME	CLASS/ SUBCLASS	FILING DATE

FOREIGN PATENT DOCUMENTS					
EXAMINER INITIAL	DOCUMENT NO.	PUBLICATION DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES NO

OTHER PRIOR ART (including author, title, date, pertinent page, etc.)	
<i>MLL</i>	B. Prince, <u>Semiconductor Memories: A Handbook of Design, Manufacture, and Application, 2nd edition</u> , John Wiley & Sons, pp. 182-187, 07/1996.
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<i>MLL</i>	Amin, "Design, selection, and implementation of flash erase EEPROM memory cells", <u>IEE Proceedings-G</u> , v. 139, n. 3, pp. 370-376, 06/1992.
<i>MLL</i>	Forbes, "Use of a spreadsheet for Fowler-Nordheim equation calculations", <u>J. Vac. Sci. Technol. B</u> , v. 17, n. 2, pp. 534-541, Mar/Apr. 1999.
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<i>MLL</i>	Chi et al., "True Low-Voltage Flash Memory Operations", <u>Proceedings of 1996 Intl. Nonvolatile Memory Technology Conference</u> , pp. 94-98, 04/1996.

DATE CONSIDERED 2/14/02	EXAMINER <i>Michael J. Didriju</i>
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